

**SVC FOUNDATION**

SVC President, Peter Martin, announced at the April 2006 TechCon that the SVC Board would establish a separate board to operate the SVC Foundation – a 501(c)(3) organization. We are happy to report that the SVC Board of Directors approved the necessary changes to implement a new SVC Foundation Board (SVCFB).

The new SVC Foundation Board members are: Jim Sesser – Chair (jesser@vol.com), John Felts – Vice Chair and Treasurer (felts.dna@ren.com), John Marcontonio – Secretary (jmarco@singulite.com), Paolo Rangesi – SVC Board Representative (prangesi@comcast.net), and John Fenn (johnfenn@earthlink.net).

The Mission Statement of the Foundation has been updated as well: "Support practitioners and attract new talent to the industry, primarily through the awarding of scholarships and fellowships."

The initial objectives of the new board are to promote the foundation, grow the level of scholarship funding, increase the donor base, strengthen the board with additional members, and develop a cost-efficient organization. While largely independent of the SVC Board of Directors, the intent of the Foundation is to work in harmony with the education mission of the SVC.

Donations to the Foundation may be made in the name of individuals or organizations, and, if large enough, may endow a scholarship in that name.

Three separate levels of donation will be recognized:  
 1. Endowed Fund: Donations in this category will be recognized when made in an amount of at least \$25,000. These donations are

intended to remain in the fund and only the interest accrued will be awarded.

2. Restricted Fund: Minimum donation for access to this fund is \$5,000. These donations will be paid-out in one or multiple awards, depending on the amount.

3. General Fund: All other donations will be pooled into this fund. We have also secured a matching grant from the SVC for qualified donations, up to a total of \$30,000.

In the last 12 months we have received several donations including a \$60,000 donation from John B. Fenn (some of you will remember him from the Plenary Session two years ago at the SVC TechCon), \$30,000 from the SVC, and \$5,000 from the SVC Foundation GK Run (organized by Wolfgang Decker). We will be announcing additional donations in this newsletter, on our section of the SVC Website at <http://www.svc.org/SF/SVCFoundationSchol.html> and at the SVC TechCon.

We have a lot of work to do in the coming months and will update the membership on our progress. If you are interested in helping with fundraising or evaluating applications for scholarships, please contact one of the current board members.

If you would like to make a donation to help us move forward, please send it to the SVC Headquarters at 71 Pinon Hill Place, Albuquerque, NM 87122 USA. The funds will be forwarded to the SVC Foundation Manager. Please make the check payable to the SVC Foundation.

John Felts, Nano Scale Surface Systems, Inc. (505)314-0390, felts.dna@nss.com is the SVC Foundation Vice Chair.

**Studying Vacuum Coating Technology or a related field?**

You could qualify for a **Scholarship** from the Society of Vacuum Coaters Foundation.

**Society of Vacuum Coaters Foundation, Inc.**  
 is accepting applications to the **Scholarship Fund**

This fund was established to assist selected individuals further their education in a course of study important to vacuum coating technology.

**Deadline for applications is January 31**

For more information or an application, visit <http://www.svc.org/SF/SVCFoundationSchol.html>

**NEW! High Density RF Plasma Deposition System**

SCT's newest system incorporates patented plasma launch technology to generate a high density, highly energetic gas plasma. The technology allows high deposition rate, high yield sputtering of a range of elements, compounds and alloys, including the notoriously difficult ferromagnetic and dielectric materials. The system is also capable of very low rate deposition, while still maintaining excellent control of the product's properties and characteristics. It is capable of generating stable plasma densities from  $10^{18}$  to in excess of  $10^{19}$  cm<sup>-3</sup> and can control layer thickness down to 1 angstrom and achieve 90% target utilization.

Ideally suited for plasma assisted deposition in:

- Photovoltaics
- Media Storage and Retrieval
- Optical Telecoms
- Precision Optics
- Semiconductors
- Research and Development

- Plasma Etching
- PECVD
- Metal/Dielectric Sputtering

Sputtering benefits include: High Target Utilization, Thick Ferromagnetic Targets, High Rate Reactive Processes, Low Stress Films, Near Bulk Densities

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